



Edwards STP-H301C Technical Specifications

Inlet flange size	ISO100K	
Pumping speed N ₂ /H ₂	300/200	Litres/second
Compression ratio N ₂ /H ₂	>10 ⁸ / 10 ³	
Ultimate pressure	10 ⁻⁷ (10 ⁻⁹)	Pa (Torr)
Maximum continuous outlet pressure*	665 (5)	Pa (Torr)
Maximum Nitrogen throughput*	2500 (4.2)	sccm (Pa m ³ /sec)
Rated speed	48000	rpm
Starting time	4	minutes
Maximum inlet flange temperature [†]	120	°C
Power consumption (Max, without TMS)	600	VA
Input voltage	100-240	V
Weight, pump/controller	15/9	kg

* water cooled † with cooling

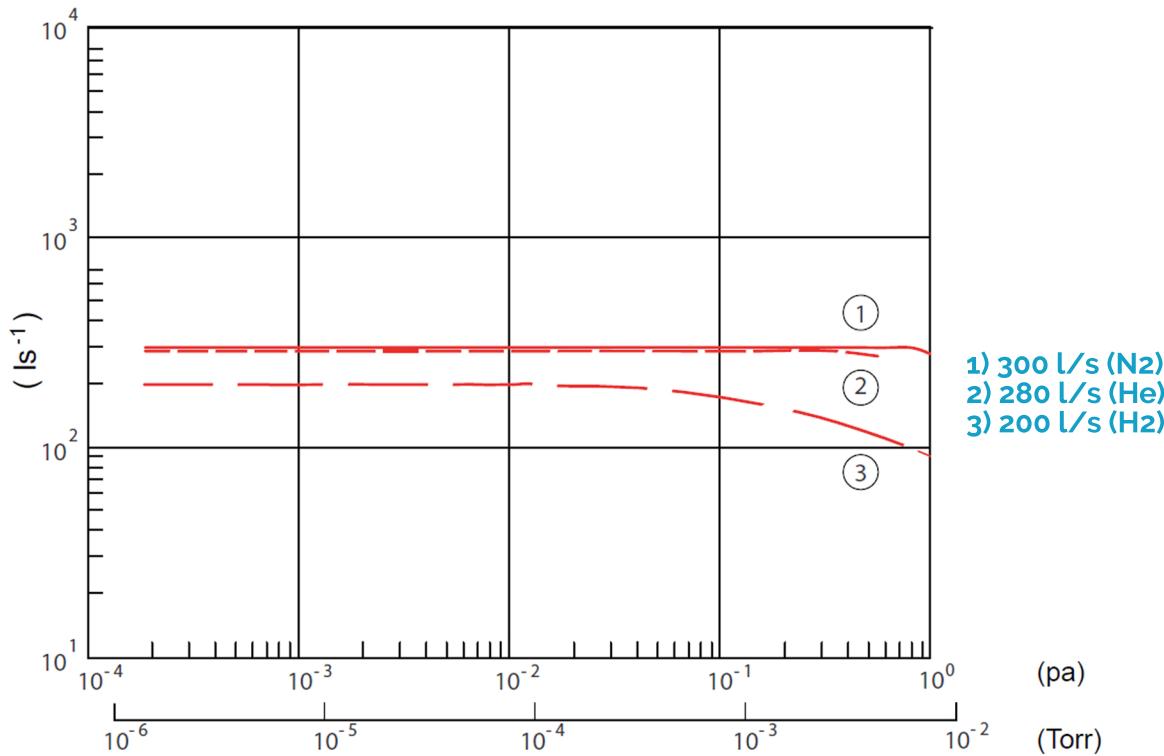




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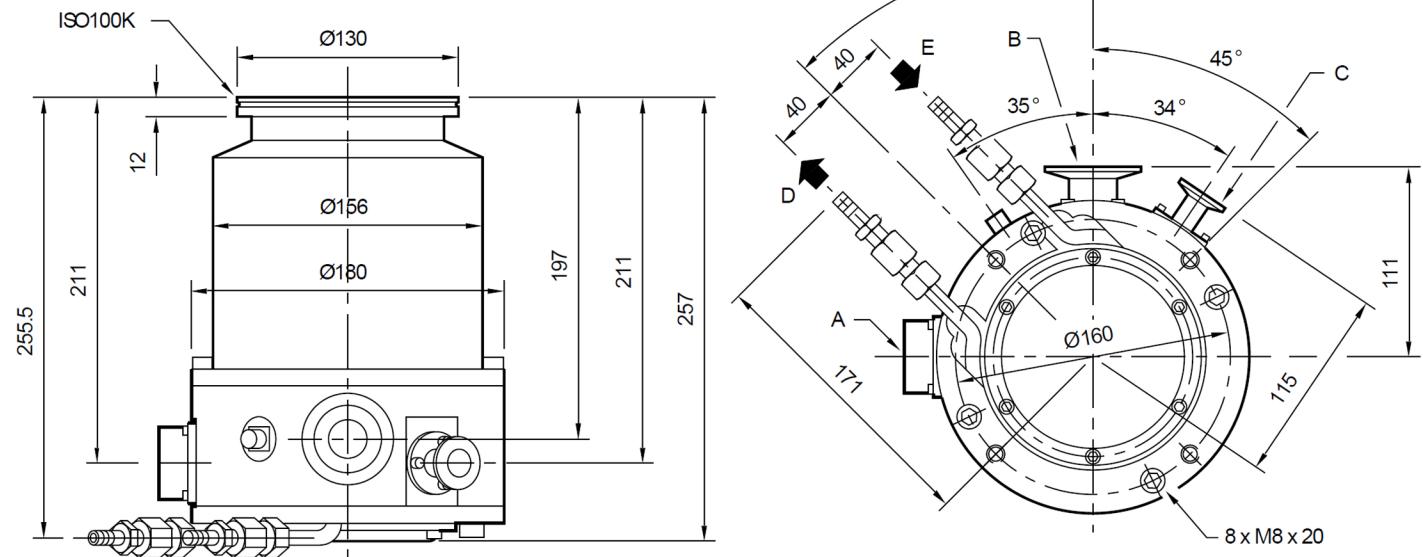
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Edwards STP-H301C Pumping Curves



- 1) 300 L/s (N₂)
- 2) 280 L/s (He)
- 3) 200 L/s (H₂)

Dimensions





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Features & Benefits

- designed for use in the harshest of semiconductor applications
- advanced half rack controller design with self-diagnostic functions
- advanced rotor technology
- higher gas throughput
- low noise & vibration
- maintenance free, increased life
- compact design, small footprint
- 5-axis magnetic suspension system
- operation in any orientation
- oil free, zero contamination

Applications

- plasma etch • ECR etch • film deposition • sputtering • ion implantation source • beam line pumping end station • MBE • diffusion • photo resist stripping • crystal, epitaxial growth • wafer inspection • load lock chambers • surface analysis • mass spectrometry • electron microscopy • high energy physics • semiconductor